

## DESIGN PARAMETERS FOR THE CADMP POWER DEVICE

### Constraints

Package type	Quad Flat Pack	
Material type	Ceramic	
Minimum I/O Pitch	10 mils	
Maximum I/O Pitch	100 mils	
Max allowable package length	1000 mils	
Max allowable package width	1000 mils	
Max allowable package height	400 mils	
Number of substrates		0
Mounting packaging material	PWBMATR.FR4	

### Semiconductor Device

Element ID	SEM 1	
Element Name	SEM 1	
Stacked	NONE	
Element Orientation	Flat	
Element material	DIEMATR.SI	
Semiconductor Technology	MOSFET	
Interconnect Technology	Al_wire	
Interconnection to:	SUBSTRATE	
Power Dissipation	150 watts	
Element Length	275 mils	
Element Width	275 mils	
Element Thickness	15 mils	
Bond Pad Material	METAMATR.AL	
Bond Pad Pitch	50 mils	
Bond Pad Length	40 mils	
Bond Pad Thickness	0.5 mils	
Bond Pad Width	40 mils	
High Output Voltage	99 volts	
Low Output Voltage	1 volt	
High Input Voltage	19 volts	
Low Input Voltage	1 volt	
Clock frequency	33 MHz	
Bandwidth	250 MHz	
Worst case current density	1 E 06 A/cm2	
Avalanche breakdown voltage	50 volts	
Internal bulk resistance	8 ohms	
Thermal breakdown energy	1000 J	
Input junction energy	5 J	
Voltage (source-to-drain)	100 volts	
Potential drop		0
Carrier concentration	1 E 20	
Doping density	1 E 20	
Poly width		0
Diffusion length		0
Initial vertical crack depth	0.5 mils	

Final vertical crack depth	1 mils
Initial horizontal crack depth	0.5 mils
Final horizontal crack depth	1mils
Min. distance between tracks	0.08 mils
Passivation Deposition Temp	475 C
Gate oxide thickness	500 angstroms
Effective oxide thickness	400 angstroms
Horiz elliptical crack length	2mils
Horiz elliptical crack depth	1mils
Vertical elliptical crack length	2 mils
Vertical elliptical crack depth	1 mils
Metallization material	METAMATR.AL
Max metallization length	250 mils
Max metallization width	0.08 mils
Max metallization thickness	0.04 mils
Maximum crack width	0.4 mils
Grain boundary width	0.4 mils

**Device Placement**                      **CENTER**

**Device Attach**

Attach material	ATTAMATR.AUSI
Initial Horiz. Crack Depth	0.25 mils
Final Horiz. Crack Depth	1 mil
Half Horiz. Crack Length	0.5 mils
Bonding Temperature	363 C
<b>Attach thickness</b>	<b>1.5 mils</b>

**Lead**    **FLAT LEAD**

Lead Select	Deselect all leads on the top and bottom Deselect the third and seventh lead on each side
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Lead/Pin Pitch	65 mils
Min Lead Margin	0 mils
Solder Length	65 mils
Solder Width	65 mils
Solder Height	2 mils

**Lead Designer**

Lead material	LEADMATR.CU194
Solder material	SOLDER.SNPB3
Lead length	100 mils
Lead width	65 mils
Lead thickness	10 mils

**Lead Seal**

Lead seal material	ATTAMATR.EPOXYN
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Lead seal thickness 10 mils

### Lid

Lid material LIDMATR.AL2O3  
Lid ring width 0 mils  
Lid ring length 0 mils  
Lid ring thickness 20 mils

Lid width 600 mils  
Lid thickness 20 mils

### Lid Seal

Lid seal material ATTAMATR.EPOXYN  
Lid seal thickness 10 mils

### Case

Case width 600 mils  
Case thickness 60 mils  
Inner case width 550 mils  
Inner case thickness 25 mils  
Wall material HERMMATR.AL2O3N  
Header material HERMMATR.BEO  
Header attach material ATTAMATR.EPOXYN  
Header attach thickness 10 mils  
Leak rate 1 E -12 Pa/m3s

Radioactive Element Conc 0

### Interconnect Design Al\_wire

Wire material WIREMATR.AL  
Bond type WEDGE  
Length of the wire bond 4 mils  
Wire span 50 mils  
Wire diameter 5 mils  
Wire length 70 mils  
Initial radius of curvature 10 mils  
Angle of wire contact (far end) 30 degrees